

## Supplementary Information

### Giant Spin Seebeck Effect through an Interface Organic Semiconductor

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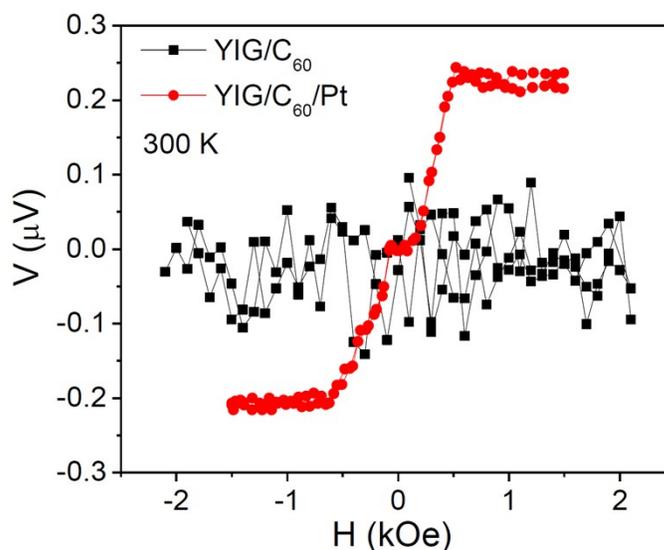
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#### S1. Anomalous Nernst effect measurement on the YIG/C<sub>60</sub> structure



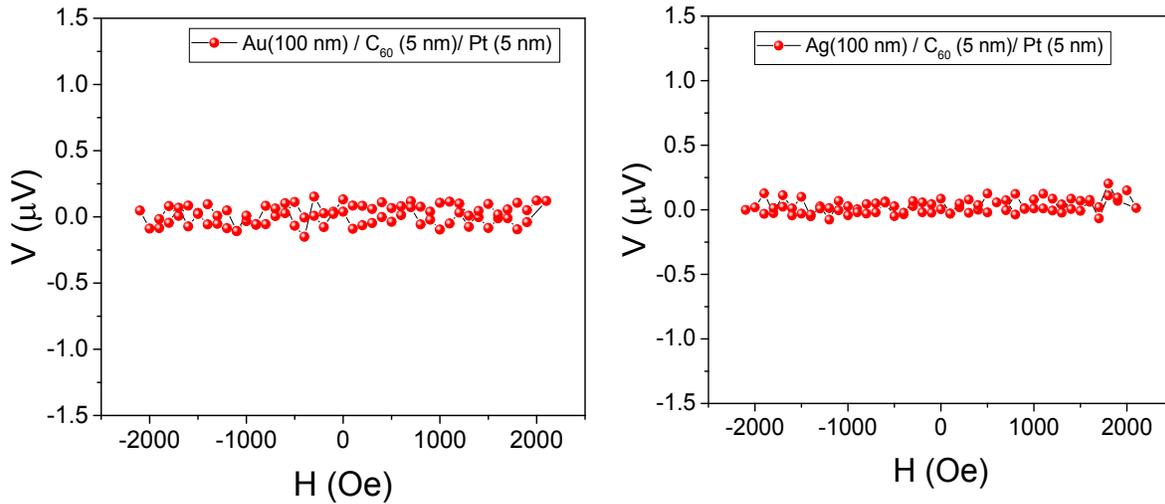
**Fig. S1.** ISHE voltage vs. magnetic field data taken at 300 K for the YIG/C<sub>60</sub> and YIG/C<sub>60</sub>/Pt structures.

We tested Anomalous Nernst effect (ANE) in the YIG/C<sub>60</sub> structure, as shown in Fig. S1. It can be seen that the ANE signal is very weak and noisy. Also the low field anomaly of the  $V_{LSSE}$  vs.  $H$  curves observed in Figure 4a and b (also included in Fig. S1 for comparison) is due to the surface anisotropy of YIG. Since there is no anomalous Nernst effect present in YIG/C<sub>60</sub>, the  $V_{LSSE}$  signals we have observed in YIG/C<sub>60</sub>/Pt are dominated by the LSSE.

## S2. ISHE voltage vs. magnetic field measurements on the C<sub>60</sub>/Pt structure

To test if there is any considerable contribution to the LSSE (the  $V_{ISHE}$  signal obtained from Pt layer) from the Pt/C<sub>60</sub> surface, we have fabricated two reference samples of SiO<sub>2</sub>/Au (100 nm)/C<sub>60</sub> (5 nm) / Pt (5 nm) and SiO<sub>2</sub>/Ag (100 nm)/C<sub>60</sub> (5 nm) / Pt (5 nm) and performed ISHE voltage vs. magnetic field measurements on these samples.

The Si/SiO<sub>2</sub> (300 nm) substrates were cleaned by a standard chemical cleaning procedure using soap, distilled water, acetone, and isopropanol in an ultrasonic bath. 2 nm of Cr was deposited first to enhance the adhesion between the silicon substrate and the Au/Ag layers. Both of the Cr (2nm) and Au/Ag (100nm) layers were deposited using an electron beam evaporator at a rate of 0.5 Å/s in a base pressure of  $\approx 2 \times 10^{-7}$  torr. Without breaking the vacuum, a layer of 5nm C<sub>60</sub> was deposited using thermal evaporation method. The material was evaporated at a rate of 0.2 Å/s at a temperature of 520 degrees Celsius, and  $2 \times 10^{-7}$  torr of pressure. 5 nm of platinum was then sputtered on top as mentioned in the manuscript.



**Fig. S2.**  $V_{ISHE}$  vs.  $H$  data obtained from Pt layer at 300 K for Si/SiO<sub>2</sub>/Au(100nm)/ C<sub>60</sub> (5nm)/Pt(5nm) and Si/SiO<sub>2</sub>/Ag(100nm)/ C<sub>60</sub> (5nm)/Pt(5nm).

All measurements were performed at the same conditions as the YIG/C<sub>60</sub>/Pt measurements by creating a  $\sim 2$ K temperature gradient across the samples. As can be seen in **Fig. S2**, both reference samples do not pick up any significant signal beyond the noise level. This confirms that the C<sub>60</sub>/Pt interface does not contribute to the LSSE signal measured from Pt in **Figure 4**.